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**Serial Number: 10552152**

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PALM INTRANET

# Inventor Information for 10/552152

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US 20060194055 A1	20060831	Process for production of water-absorbing resin particles	428/402	523/336	Matsuda; Kenya et al.
US 20060189953 A1	20060824	Water-absorbing resin composition	604/360	521/50; 604/372	Taniguchi; Takayasu et al.
US 20060074160 A1	20060406	Water-absorbing resin composition	524/284	524/420; 524/556	Handa; Masayoshi et al.
US 20050096904 A1	20050505	Signal processing apparatus and mobile radio communication terminal	704/226		Taniguchi, Takayuki et al.
US 20050085604 A1	20050421	Process for producing water-absorbing resin	526/227	526/317.1	Handa, Masayoshi et al.
US 20030153887 A1	20030814	Water-absorbing resin suitable for absorbing viscous liquids containing high-molecular compound, and absorbent and absorbent article each comprising the same	604/372		Nawata, Yasuhiro et al.
US 20010055853 A1	20011227	PROCESS FOR FABRICATING A SEMICONDUCTOR DEVICE	438/424	257/E21.548; 438/425; 438/426; 438/427; 438/428; 438/430; 438/435; 438/437	TANIGAMI, TAKUJI et al.
US 20010041976 A1	20011115	Signal processing apparatus and mobile radio communication terminal	704/226		Taniguchi, Takayuki et al.
US 7058574 B2	20060606	Signal processing apparatus and mobile radio communication terminal	704/233		Taniguchi; Takayuki et al.
US 6573330 B1	20030603	Process for preparing water-absorbent resin	525/54.31	525/191; 525/192; 525/218;	Fujikake; Masato et al.

				525/221; 525/225; 525/227; 525/64	
US 6400694 B1	20020604	Duplex communication path switching system	370/276	370/241; 714/717	Taniguchi; Takayuki
US 6395619 B2	20020528	Process for fabricating a semiconductor device	438/424	257/E21.548; 438/427	Tanigami; Takuji et al.
US 5661720 A	19970826	Multi-ring network having plural rings connected by node	370/223	370/242; 370/248; 370/403; 370/465	Taniguchi; Takayuki
US 5480047 A	19960102	Method for forming a fine resist pattern	216/12	216/24; 216/41	Tanigawa; Makoto et al.
US 5369655 A	19941129	Output control method for laser system	372/29.02	372/29.012	Miyamoto; Yasuaki et al.
US 5353116 A	19941004	Defect inspection system for phase shift masks	356/390		Tanigawa; Makoto et al.
US 5330862 A	19940719	Method for forming resist mask pattern by light exposure having a phase shifter pattern comprising convex forms in the resist	430/5	430/322; 430/326	Tabuchi; Hiroki et al.